FIG. 2

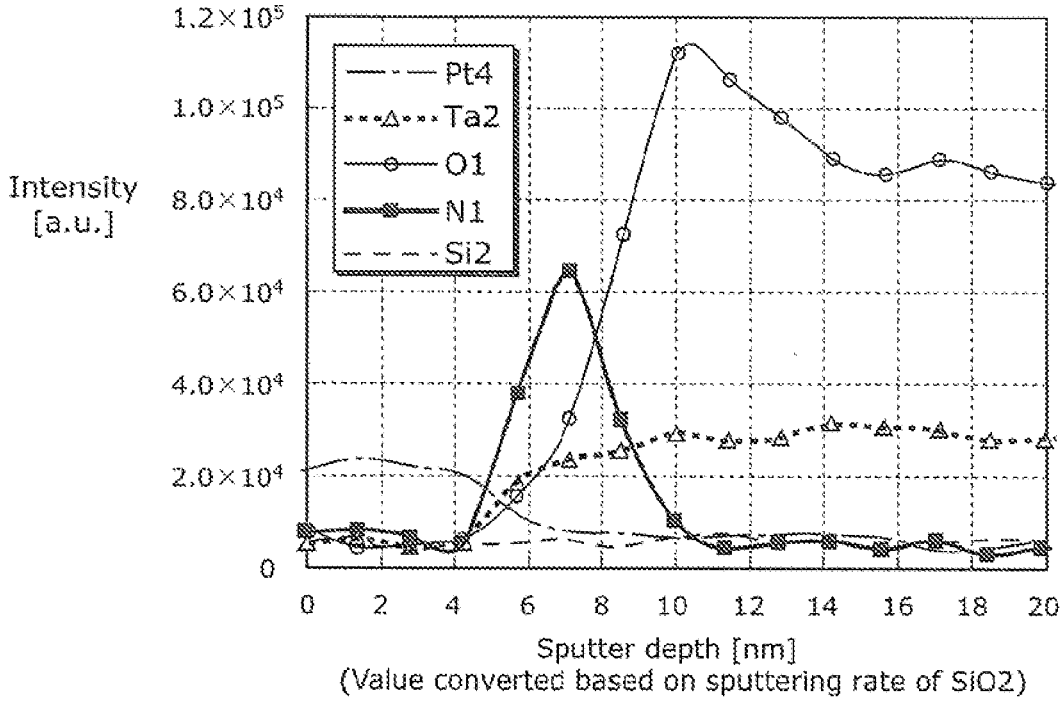
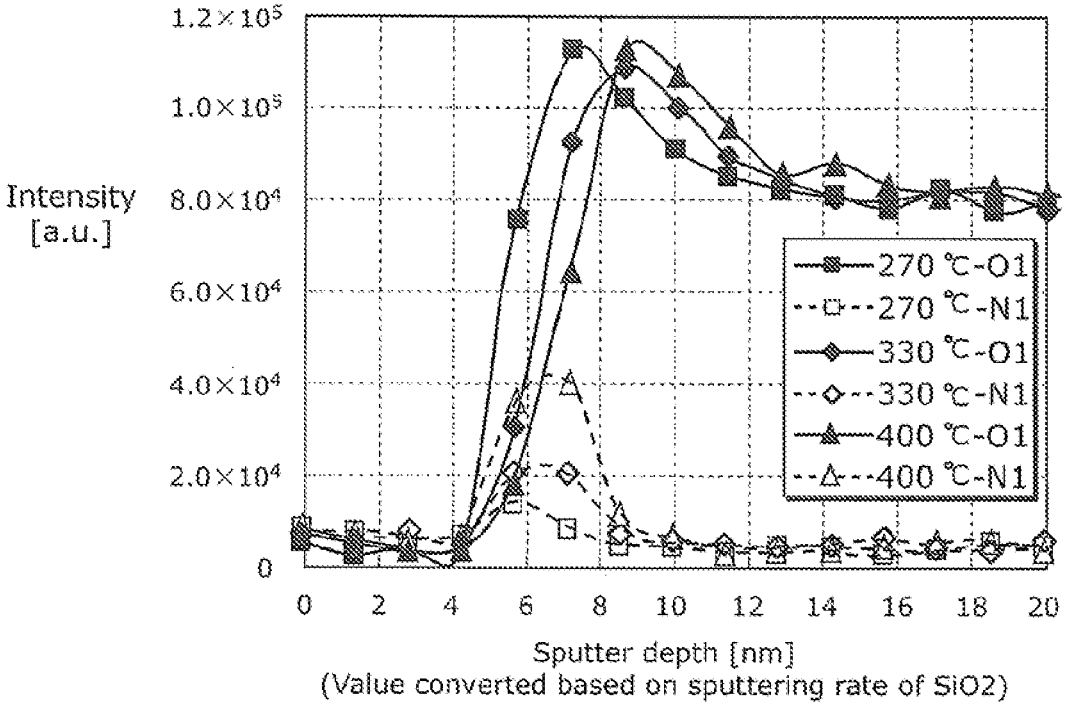

1.2×10^5
1.0×10^5
8.0×10^4
6.0×10^4
4.0×10^4
2.0×10^4
0
Intensity [a.u.]
Pt4
Ta2
O1
N1
Si2
0 2 4 6 8 10 12 14 16 18 20
Sputter depth [nm]
(Value converted based on sputtering rate of SiO2)

FIG. 3


1.2×10^5
1.0×10^5
8.0×10^4
6.0×10^4
4.0×10^4
2.0×10^4
0
Intensity [a.u.]
270 ℃-O1
270 ℃-N1
330 ℃-O1
330 ℃-N1
400 ℃-O1
400 ℃-N1
0 2 4 6 8 10 12 14 16 18 20
Sputter depth [nm]
(Value converted based on sputtering rate of SiO2)